

## AMENDMENTS TO THE CLAIMS

1-9 (canceled)

10. (original) A carrier for planarizing a first surface of a work piece comprising:

a carrier housing;

a circular work piece bladder having a surface configured to press against a second surface of a work piece;

a circular clamp surrounding the work piece bladder and coupling the work piece bladder to the carrier housing;

a wear ring coupled to the carrier housing and surrounding the work piece bladder, the wear ring having a cross sectional shape configured to allow an inner diameter of the wear ring to be spaced near an edge of the work piece bladder and to avoid contact between the wear ring and the circular clamp.

11. (original) The carrier of claim 10 wherein the wear ring comprises a toroidal structure having a thick portion at the outer periphery thereof and a thinner portion at the inner diameter thereof.

12. (original) The carrier of claim 11 further comprising a wear ring diaphragm coupling the wear ring to the carrier housing and partially enclosing a wear ring plenum in which the pressure can be adjusted.

13-25 (canceled)

26. (currently amended) A method for planarizing a first surface of a work piece utilizing a CMP apparatus comprising: a polishing pad; a work piece diaphragm supported by at least an outermost pressure adjustable member aligned with an extreme outer perimeter of the work piece, and having a first surface for pressing against a second surface of the work piece; at least one pressure adjustable web plenum positioned adjacent a second surface of the work piece diaphragm; and a wear ring surrounding the work piece diaphragm and configured to press against the polishing pad, the pressure with which the wear ring presses

against the polishing pad being adjustable, the method comprising the steps of:

- positioning a second surface of a work piece adjacent the first surface of the work piece diaphragm;
- establishing a predetermined pressure in the at least one web plenum;
- pressing the wear ring against the polishing pad with a predetermined [forece] force;
- adjusting independent of the predetermined force, the pressure of the outermost pressure adjustable member; and
- initiating relative motion between the work piece diaphragm and the polishing pad.

27. (currently amended) The method for planarizing a first surface of a work piece of claim 26, further comprising the steps of:

- measuring the material removal profile across the first surface of the [workpiece] work piece; and
- adjusting at least one of the wear ring pressing force, the pressure of the outermost pressure adjustable member, and the web plenum pressure based on the material removal profile measurement.

28. (original) The method for planarizing a first surface of a work piece of claim 26, wherein the outermost pressure adjustable member comprises a rib and pressure adjustable carrier plenum associate therewith.

29. (original) The method for planarizing a first surface of a work piece of claim 28, wherein the at least one pressure adjustable web plenum comprises a plurality of pressure adjustable web plenums positioned against the second surface of the work piece diaphragm.